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(54) **Spring structure**

(57) A stress-balancing layer (130) is formed over portions (122) of a spring metal finger (120) that remain attached to an underlying substrate (101) to counter internal stresses inherently formed in the spring metal finger (120). The (e.g., positive) internal stress of the spring metal causes the claw (tip) (125) of the spring metal finger (120) to bend away from the substrate (101) when an underlying release material is removed. The stress-balancing pad (130) is formed on an anchor portion (122) of the spring metal finger (120), and includes

an opposite (e.g., negative) internal stress that counters the positive stress of the spring metal finger (120). A stress-balancing layer (230) is either initially formed over the entire spring metal finger (120) and then partially removed (etched) from the claw portion (125), or selectively deposited only on the anchor portion (122) of the spring metal finger (120). An interposing etch stop layer (325-1) is used when the same material composition is used to form both the spring metal (220) and stress-balancing (230) layers.

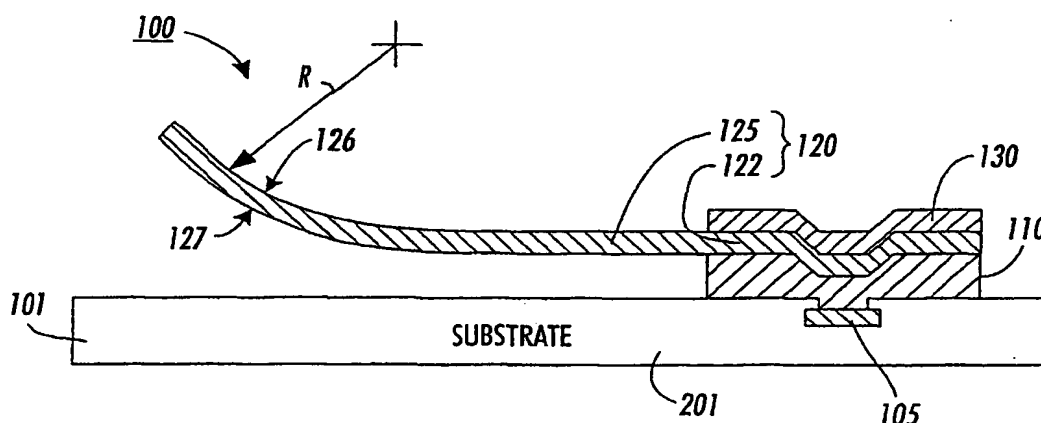


FIG. 2

Description

[0001] Photo lithographically patterned spring structures (sometimes referred to as "micro-springs") have been developed, for example, to produce low cost probe cards, and to provide electrical connections between integrated circuits. A typical spring includes a spring metal finger having a flat anchor portion secured to a substrate, and a curved claw extending from the anchor portion and bending away from the substrate. The spring metal finger is formed from a stress-engineered metal film (i.e., a metal film fabricated such that its lower portions have a higher internal compressive stress than its upper portions) that is at least partially formed on a release material layer. The claw of the spring metal finger bends away from the substrate when the release material located under the claw is etched away. The internal stress gradient is produced in the spring metal by layering different metals having the desired stress characteristics, or using a single metal by altering the fabrication parameters. Such spring metal structures may be used in probe cards, for electrically bonding integrated circuits, circuit boards, and electrode arrays, and for producing other devices such as inductors, variable capacitors, and actuated mirrors.

[0002] In accordance with the present invention, the strength and durability of a spring structure is increased by providing a stress-balancing pad formed on the unlifted anchor portion of the spring metal finger, where the stress-balancing pad is formed with an internal stress gradient (and stress moment) that is opposite in sign to the internal stress gradient (and stress moment) of the spring metal finger. Specifically, in contrast to the spring metal finger, the stress-balancing pad is formed from a stress-engineered metal film fabricated such that portions furthest from the anchor portion have a higher internal compressive stress than portions closest to the anchor portion. This opposite internal stress gradient causes the stress-balancing pad to apply a downward force on the edges of the anchor portion, thereby resisting the delamination or peeling of the anchor portion that can result in separation from an underlying substrate. In one embodiment, the internal stress gradient (and moment) of the stress-balancing pad has a magnitude that is equal to or greater than the internal stress gradient (and moment) of the spring metal finger, thereby preventing delamination or peeling of the anchor portion by completely countering (nullifying) the internal stress (and moment) of the spring metal finger.

[0003] Particular embodiments in accordance with this invention will now be described with reference to the accompanying drawings; in which:-

Fig. 1 is a plan view showing a spring structure according to a first embodiment of the present invention;

Fig. 2 is a cross-sectional side view of the spring structure taken along section line 2-2 of Fig. 1, and

the spring structure contacting a separate integrated circuit;

Fig. 3 is a cut-away perspective view of the spring structure shown in Fig. 1;

Fig. 4 is a partial side view showing internal stresses formed in respective layers of the spring structure shown in Fig. 1;

Figs. 5(A) through 5(K) are cross-sectional side views showing fabrication steps associated with the production of the spring structure shown in Fig. 1 according to a first method;

Figs. 6(A) through 6(M) are cross-sectional side views showing fabrication steps associated with the production of an alternative spring structure according to a second method; and,

Figs. 7(A) through 7(L) are cross-sectional side views showing fabrication steps associated with the production of the spring structure shown in Fig. 1 according to a third method.

[0004] As used herein, the terms "spring metal" and "stress-balancing" are used to identify stress-engineered metal structures fabricated with opposite internal stress gradients. In particular, the term "spring metal layer" identifies a metal film fabricated such that its lower portions (i.e., closest to a support substrate) have a higher internal compressive stress than its upper portions. In contrast, the term "stress-balancing layer" identifies a metal film fabricated such that its lower portions (i.e., closest to substrate 101) have a lower internal compressive stress than its upper portions (i.e., such that the stress-balancing layer has an internal stress gradient that is opposite to that of the spring metal layer). Note that a portion of the intrinsic stress in either layer may be tensile. In addition, the term "island" is used to refer to patterned layer portions prior to the release process. For example, the term "spring metal island" refers to a patterned portion of the spring metal layer including an unreleased (unlifted) claw portion and an anchor portion, whereas the term "spring metal finger" refers to the same patterned portion after the claw is released. Similarly, the terms "stress-balancing island" and "release material island" refer to patterned portions of the stress-balancing layer and a release material layer that are located over and under the spring metal island, respectively.

[0005] Figs. 1, 2, 3, and 4 show a spring structure 100 according to a first embodiment of the present invention. Spring structure 100 generally includes a substrate 101, a support pad 110, a spring metal finger 120, and a stress-balancing pad 130. Substrate 101 (e.g., glass) includes an optional conductor 105 that can take several forms (i.e., a metal line deposited on the substrate or a buried conductor accessed by an opening in a passivation layer). When present, conductor 105 may provide electrical connection between electronic components of an integrated circuit and spring structure 100. Alternatively, if substrate 101 is printed circuit board, printed

wiring board, silicon device, or interposer, then conductor 105 may be an exposed portion of conducting material that is electrically connected to redistribution traces, through substrate vias, solder bumps, solder balls, mounted electrical components, integrated passive components, or interconnect pads.

[0006] Support pad 110 is formed on an upper surface of substrate 101 such that it contacts conductor 105 (if present). In one embodiment, support pad 110 is formed from a release material layer that is partially sacrificed to release a claw portion 125 of spring metal finger 120. When formed from release material, support pad 110 may be titanium that is sputter deposited onto substrate 101 to a thickness of approximately 50 nm or greater. Titanium provides desirable characteristics as a release material layer due to its plasticity (i.e., its resistance to cracking). Other release materials having the beneficial plastic characteristics of titanium may also be used. In other embodiments, support pad 110 includes another metal, such as Copper (Cu), Aluminum (Al), Nickel (Ni), Zirconium (Zr), or Cobalt (Co). By selecting a conductive release material, support pad 110 provides electrical connection between spring metal finger 120 and conductor 105 (when present). In another embodiment, support pad 110 may be formed from a non-conducting release material, and a strap or other conducting structure may be formed between spring metal finger and an exposed conductor. In yet another embodiment, support portion 110 may be formed from a material different from the release material by separately patterning the release material and support portion 110 using known techniques.

[0007] Spring metal finger 120 includes an anchor portion 122 and a claw (i.e., cantilevered portion) 125. Anchor portion 122 is attached to substrate 101 via support pad 110 (i.e., such that support pad 110 is located between anchor portion 122 and substrate 101). Claw 125, which includes a tip 125-T, extends from anchor portion 122 over substrate 101. Spring metal finger 120 is etched from a stress-engineered metal film that is deposited by DC magnetron sputtering one or more metals using gas (e.g., Argon) pressure variations in the sputter environment during film growth. These pressure variations are controlled using known techniques to generate an internal stress gradient that causes claw 125 to bend away from substrate 101 when an underlying release material is removed. Note that although much of this internal stress gradient is essentially relieved in the lifted claw 125, anchor portion 122 retains a substantial amount of internal stress.

[0008] The present inventors recognized that most failures of spring structures (i.e., separation of the spring structure from an underlying substrate through delamination or peeling) occur a significant amount of time after fabrication.

[0009] In accordance with an aspect of the present invention, stress-balancing pad 130 is formed on anchor portion 122 of spring metal finger 120 to counterbalance

the internal stress gradient tending to separate (e.g., delaminate or peel) anchor portion 122 from support pad 110. Similar to spring metal finger 120, stress-balancing pad 130 is formed using a stress-engineered metal film that is deposited by DC magnetron sputtering one or more metals using gas pressure variations in the sputter environment during film growth. However, stress-balancing pad 130 is formed using a pressure variation sequence that is opposite to that utilized to generate spring metal finger 120, thereby causing stress-balancing pad 130 to include an internal stress that is opposite to that provided in spring metal finger 120. In one embodiment, the opposite stress gradient is achieved by beginning the deposition process under conditions known to produce tensile stress, and then lowering the deposition sputter pressure in one or more steps to add one or more layers that are more compressive. Ideally, the layers are engineered to produce a metal stack with zero net stress and zero net moment. Accordingly, stress-balancing pad 130 exerts a downward force (i.e., toward substrate 101) on the edges of anchor portion 122 that counterbalances the upward force generated by the internal stress gradient of spring metal finger 120, thereby resisting delamination or separation of anchor portion 122 from substrate 101.

[0010] Fig. 4 is partial side view in which internal stress gradients are superimposed over portions of anchor portion 122 and stress-balancing pad 130. As indicated in the lower portion of Fig. 4, anchor portion 122 is etched from a stress-engineered metal film that has a positive stress gradient $\Delta\sigma+$ (i.e., tending to bend the edges of anchor portion 122 away from substrate 101), whereas stress-balancing pad 130 is etched from a stress-engineered metal film that has a negative stress gradient $\Delta\sigma-$ (i.e., tending to bend the edges of stress-balancing pad 130 downward toward substrate 101). According to an embodiment the present invention, the negative stress gradient (and resulting stress moment) of stress-balancing pad 130 is equal in magnitude to or greater in magnitude than the positive stress gradient (and resulting stress moment) of anchor portion 122 such that zero net stress (and zero peeling moment) exists at an upper surface 131 of stress-balancing pad 130 is essentially nullified or slightly negative, thereby reliably preventing the separation of anchor portion 122. However, in other embodiments the stress gradient magnitude of stress-balancing pad 130 may be less than that of anchor portion 122 and still prolong the operational lifetime of spring structure 100 beyond that of conventional structures produced without stress-balancing pad 130.

[0011] Figs. 5(A)-5(K), 6(A)-6(M), and 7(A)-7(L) are cross-sectional side views illustrating three methods for fabricating spring structures incorporating the stress-balancing pad of the present invention.

[0012] In a first method, shown in Figs. 5(A)-5(K), both a spring metal layer and a stress-balancing layer are deposited/grown before the spring metal finger is

processed (e.g., masked, etched and released). The first method requires a minimum number of processing steps, but typically requires forming the spring metal layer and the stress-balancing layer using different material compositions, and selectively etching a portion of the stress-balancing layer located over the claw portion of the spring metal finger.

[0013] Referring to Fig. 5(A), the first fabrication method begins with the formation of a release material layer 210 over a substrate 101 (e.g., silicon). In one embodiment, release material layer 210 is formed from an electrically conductive material, and a portion 210A of release material layer 210 contacts a conductor 105 that is exposed on the upper surface of substrate 101. In one embodiment, release material layer 210 is Titanium (Ti) that is sputter deposited onto substrate 101 to a thickness of approximately 0.2 microns or greater.

[0014] Fig. 5(B) shows a stress-engineered spring metal layer 220 formed on release material layer 210 using known processing techniques such that it includes internal stress variations in the growth direction (i.e., as shown in Fig. 4). Methods for generating such internal stress variations in spring metal layer 220 are taught, for example, in US-A-3,842,189 (depositing two metals having different internal stresses) and US-A-5,613,861 (e.g., single metal sputtered while varying process parameters). In one embodiment, which utilizes a 0.2 micron Ti release material layer, spring metal layer 220 includes Molybdenum and Chromium (MoCr) sputter deposited to a thickness of 1 micron.

[0015] Referring to Fig. 5(C), a stress-balancing layer 230 is then formed on spring metal layer 220 using gas pressure variations that generate an internal stress gradient opposite to that of spring metal layer 220. Stress-balancing layer 230 is preferably formed from a material composition (e.g., Mo having a thickness of 1 micron) that is different from that utilized to form spring metal layer 220. As discussed below, by forming stress-balancing layer 230 and spring metal layer 220 from different material compositions, selective etching may be utilized to remove portions of stress-balancing layer 230 without undesirably etching spring metal layer 220.

[0016] Fig. 5(D) shows a spring metal (first) mask 240 (e.g., photoresist) that is patterned on a selected portion of stress-balancing layer 230. Note that spring metal mask 240 extends over an associated conductor 105 (if present).

[0017] Next, as indicated in Fig. 5(E), exposed portions of the stress-balancing layer and the spring metal layer surrounding mask 240 are etched using one or more etchants 242 to form a laminated structure including a stress-balancing island 230-1 on a spring metal island 220-1. Note that this etching process is selectively performed to minimize etching of release material layer 210 that surround spring metal island 220-1. In one embodiment, a Mo stress-balancing layer and a MoCr spring metal layer are etched using a Cr etch, which does not significantly etch an underlying Ti release ma-

terial layer.

[0018] Fig. 5(F) shows a subsequent anisotropic etching process during which exposed portions of the release material layer surrounding spring metal island 220-1 are removed to form a release material island 210-1. When a Ti release material layer is used, anisotropic etching may be performed using fluorine plasma.

[0019] Referring to Figs. 5(G) and 5(H), the spring metal mask is then removed, and a release (second) mask 250 is formed that exposes a first portion 210-1A of the release material island, a first (claw) portion 220-1A of the spring metal island, and a first portion 230-1A of the stress-balancing island. In particular, release mask 250 is formed over a second portion 210-1B of the release material island, a second (anchor) portion 220-1B of the spring metal island, and a second portion 230-1B of the stress-balancing island, which, as described below, forms the stress-balancing pad of the present invention.

[0020] As shown in Fig. 5(I), an etchant 252 is then used to selectively etch the exposed first portion of the stress-balancing island, thereby forming stress-balancing pad 130. When the stress-balancing layer is Mo and the spring metal layer is MoCr, an anisotropic fluorine plasma etchant 252 is used, which does not etch claw portion 220-1B.

[0021] Subsequently, as shown in Fig. 5(J), a release etchant 254 (e.g., a buffered oxide etch to remove Ti release material) is used to selectively remove the first portion of the release material layer from beneath the claw portion of the spring metal island to form support pad 110, claw 125, and anchor portion 122. Specifically, removal of the exposed release material causes claw 125 to bend away from substrate 101 due to the internal stress variations established during the formation of the spring metal layer. Note that anchor portion 122 remains attached to substrate 101 via support pad 110, which, along with stress-balancing pad 130, is protected during the release process by release mask 250.

[0022] Finally, as shown in Fig. 5(K), the release mask is removed to complete the fabrication of spring structure 100, which is discussed above with reference to Figs. 1-4.

[0023] In an alternative to the first method described above with reference to Figs. 5(A)-5(K), spring metal layer 220 (Fig. 5(B)) is formed using Nickel-Zirconium (NiZr), and stress-balancing layer 230 (Fig. 5(C)) is formed by Ti solution hardened with Si (Ti:Si). This alternative embodiment reduces fabrication costs by allowing the stress-balancing layer etch (Fig. 5(I)) and the release process (Fig. 5(J)) to be performed simultaneously using a single Ti etchant (e.g., a buffered oxide etch) that does not etch the NiZr claw portion of the spring metal finger.

[0024] Figs. 6(A)-6(M) depict a second fabrication method that is similar to the first method in that a release material layer 310 (Fig. 6(A)), a spring metal layer 320 (Fig. 6(B)), and a stress-balancing layer 330 (Fig. 6(D))

are deposited/grown before the spring metal finger is processed. However, in accordance with the second method, stress-balancing layer 330 and spring metal layer 320 are formed from the same material, thereby reducing the number of targets required in the deposition equipment, but requiring the deposition of an etch stop layer 325, as shown in Fig. 6(C), on spring metal layer 320 and sandwiched by the subsequently-formed stress-balancing layer 330 (shown in Fig. 6(D)). One embodiment of the second method utilizes a Ti release layer 310, a Mo spring metal layer 320, a Cr etch stop layer 325, and a Mo stress-balancing layer 330.

[0025] Subsequent processing in accordance with the second method is similar to the first method. A spring metal (first) mask 340 is formed over stress-balancing layer 330 (Fig. 6(E)), and a first etchant (e.g., a Cr etch) 342 is utilized to form spring metal island 320-1, etch stop island 325-1, and stress-balancing island 330-1 (Fig. 6(F)). Subsequently, a second etchant 344 (e.g., anisotropic etching using fluorine plasma) is utilized to etch the release material layer to form a release material island 310-1 (Fig. 6(G)), and the spring metal mask is removed (Fig. 6(H)). A release mask 350 is then formed that exposes a (first) portion 330-1 of the stress-balancing layer (Fig. 6(I)), and then this first portion is removed using etchant 352 (e.g., anisotropic etching using fluorine plasma; Fig. 6(J)). An optional additional etchant 353 is then utilized, if necessary, to remove a portion 325-1A of the etch stop material from claw portion 320-1A (Figs. 6(J) and 6(K)), and then a release etchant 354 is utilized to release claw 125-A (Fig. 6(L)), which then forms a spring structure 100-A (Fig. 6(M)) having essentially the same characteristics described above with reference to Figs. 1-4.

[0026] In an alternative to the second method, the single-step island formation etch (Fig. 6(F)) is replaced with a three-step process that includes forming the Mo stress-balancing island 330-1 by anisotropically etching the stress-balancing layer using fluorine plasma, forming Cr etch stop island 325-1 using a Cr etch, and then forming the Mo spring metal island 320-1 by anisotropically etching the spring metal layer using fluorine plasma. Although this alternative increases the number of etching steps, the feature definition of the resulting spring structure may be improved over that produced using the single-step island formation process described above.

[0027] In another alternative to the second method, release material layer 310 (Fig. 6(A)) is formed using Si, spring metal layer 320 (Fig. 6(B)) is formed using MoCr, etch stop layer 325 (Fig. 6(C)) is formed using Ti, and stress-balancing layer 330 (Fig. 6(D)) is formed using MoCr. Similar to the first alternative embodiment, a three-step island formation process is utilized (Cr etch, Ti etch, Cr etch) to form stress-balancing island 330-1, etch stop island 325-1, and spring metal island 320-1, respectively. Portion 330-1A of stress-balancing island 320-1 is subsequently etched using a Cr etch, and re-

lease is performed using a Xenon-Fluoride (XeF_2) etchant 354.

[0028] Figs. 7(A)-7(L) depict a third fabrication method in a (e.g., Ti) release material layer 410 (Fig. 7(A)) and a (e.g., MoCr) spring metal layer 420 (Fig. 7(B)) are formed, masked (Fig. 7(C)) and etched (Figs. 7(D) and 7(E)) before a (e.g., MoCr) stress-balancing layer is deposited. Specifically, after forming spring metal island 420-1 and release material island 410-1 (Figs. 7(D) and 7(E)), spring metal mask 440 is removed (Fig. 7(F)), and then a (second) mask 446 is formed that covers claw portion 420-1A and exposes anchor portion 420-1B (Fig. 7(G)). The stress-balancing layer is then deposited such that a first portions 430-1A is formed on mask 446, and a second portion 430-1B is formed on anchor portion 420-1B. Mask 446 is then lifted off along with first portions 430-1A (Fig. 7(I)) using known techniques to pattern stress-balancing pad 130-B, and then a release mask 450 is formed (Fig. 7(J)) that is utilized to release claw 125-B (Fig. 7(K)), and is then removed (Fig. 7(L)) to complete the fabrication of a spring structure 100-B having essentially the same characteristics described above with reference to Figs. 1-4.

[0029] In accordance with yet another possible embodiment, three masks may be utilized to form the spring structure such that the stress balancing pad is formed before the spring metal island is etched. In particular, a release material layer, a spring metal layer, and a stress balancing layer are sequentially deposited (i.e., forming a structure similar to that shown in Figs. 5(C) and 6(C)). A first mask is then patterned and used to etch only the stress balancing layer according to known techniques, thereby forming the stress balancing pad. The spring metal layer and release layer are then etched using a second mask (i.e., similar to that shown in Figs. 5(D) and 6(D)) to form the spring metal and release material islands. A release mask (i.e., similar to that shown in Figs. 5(H) and 6(I)) is then used to etch release material located under the claw portion to release the claw. An intermediate etch stop layer may also be formed between the spring metal layer and the stress balancing layer in the manner described above.

[0030] The disclosed process examples are not intended to be limited to the specific fabrication processes and material compositions. Other structures such as passivating layers, capping layers, devices, vias etc., may be incorporated in the process flow. Further, the described embodiments utilize two layers having opposing gradients (i.e., the spring metal layer and the stress-balancing layer). However, spring structures exhibiting the same stress-nullifying benefits of the disclosed embodiments may be produced with other stress profiles (e.g., a series of stress-engineered layers that are compressive, tensile then compressive again).

Claims**1. A spring structure (100) comprising:**

a substrate (101);
 a spring metal finger (120) including an unlifted anchor portion (122) attached to the substrate (101) and a released claw portion (125) extending over the substrate (101), wherein the anchor portion (122) has a first internal stress gradient; and
 a stress-balancing pad (130) formed on the anchor portion (122) of the spring metal finger (120), wherein the stress-balancing pad (130) has a second internal stress gradient that is opposite to the first internal stress gradient.

2. A spring structure according to Claim 1, wherein the second internal stress gradient of the stress-balancing pad (130) is equal in magnitude to or greater in magnitude than the first internal stress gradient of the anchor portion (122).

3. A spring structure according to Claim 1 or 2, wherein both the spring metal finger (120) and the stress-balancing pad (130) consist essentially of a single material composition.

4. A spring structure according to Claim 3, wherein the single material composition is Molybdenum (Mo) or Molybdenum-Chromium (MoCr).

5. A spring structure according to Claim 1 or 2, wherein the spring metal finger (120) comprises a first material, and wherein the stress-balancing pad (130) comprises a second material that is different from the first material.

6. A spring structure according to Claim 5, wherein the first material consists essentially of a Molybdenum-Chromium alloy (MoCr), and wherein the stress-balancing pad (130) consists essentially of Molybdenum (Mo).

7. A spring structure comprising:

a substrate;
 a spring metal finger having an anchor portion supported by the substrate and a claw portion extending over the substrate; and
 a stress-balancing pad formed over the anchor portion of the spring metal finger,

wherein the spring metal finger is formed from a first stress-engineered material having a first internal stress moment that causes the claw portion to bend away from the substrate, and

wherein the stress-balancing pad is formed

from a second stress-engineered material having a second internal moment that opposes to the first internal stress moment.

8. A method for fabricating a spring structure (100) on a substrate (107), the method comprising:

forming a spring metal island (220) on a release material island (210) such that the spring metal island (220) has a first internal stress;
 forming a stress-balancing pad (130) only over an anchor portion (122) of the spring metal island (220), wherein the stress-balancing pad (130) has a second internal stress that is opposite to the first internal stress; and,
 selectively removing a portion of the release material island (210) located under a claw portion (125) of the spring metal island (220) such that the claw portion (125) bends away from the substrate and the anchor portion (122) remains attached to the substrate (107).

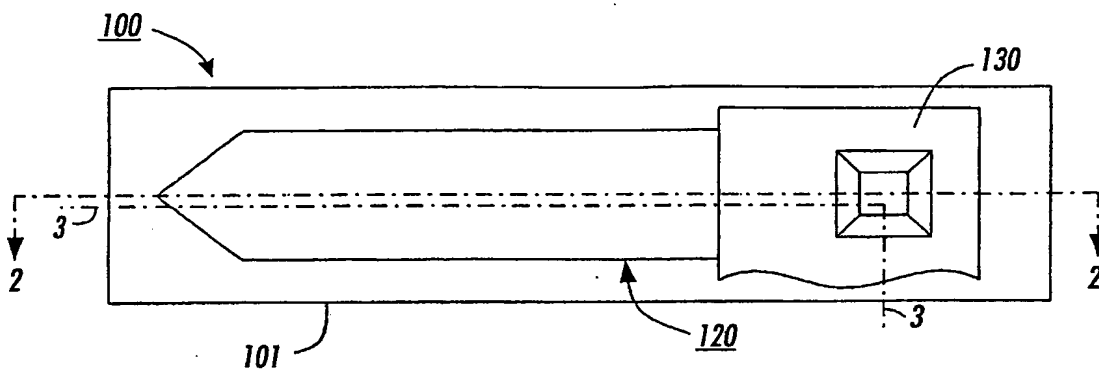


FIG. 1

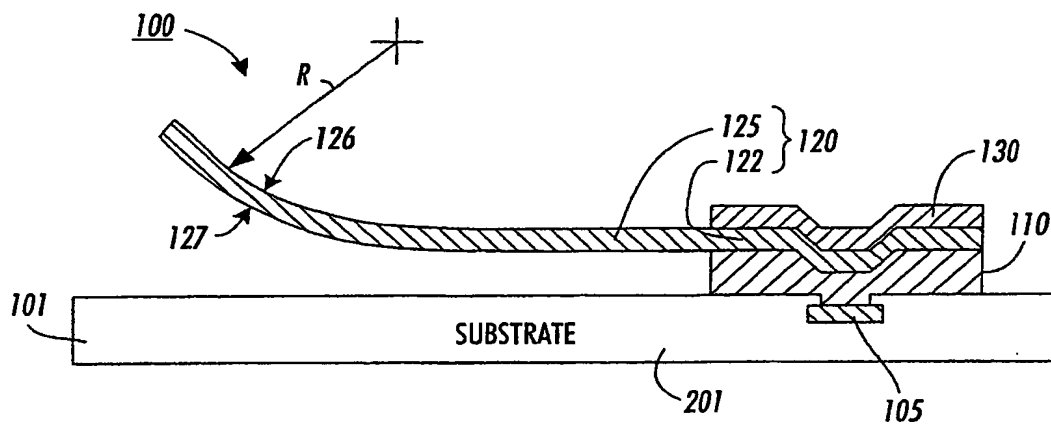


FIG. 2

FIG. 3

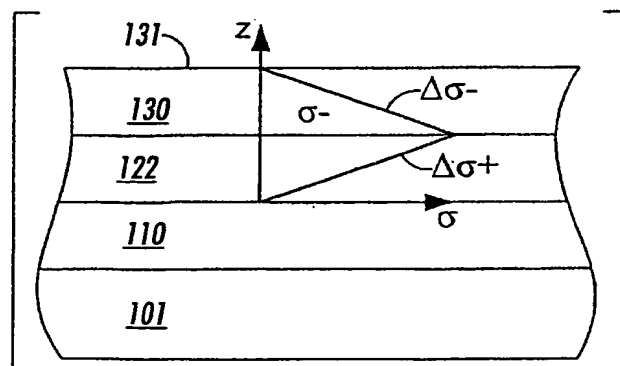
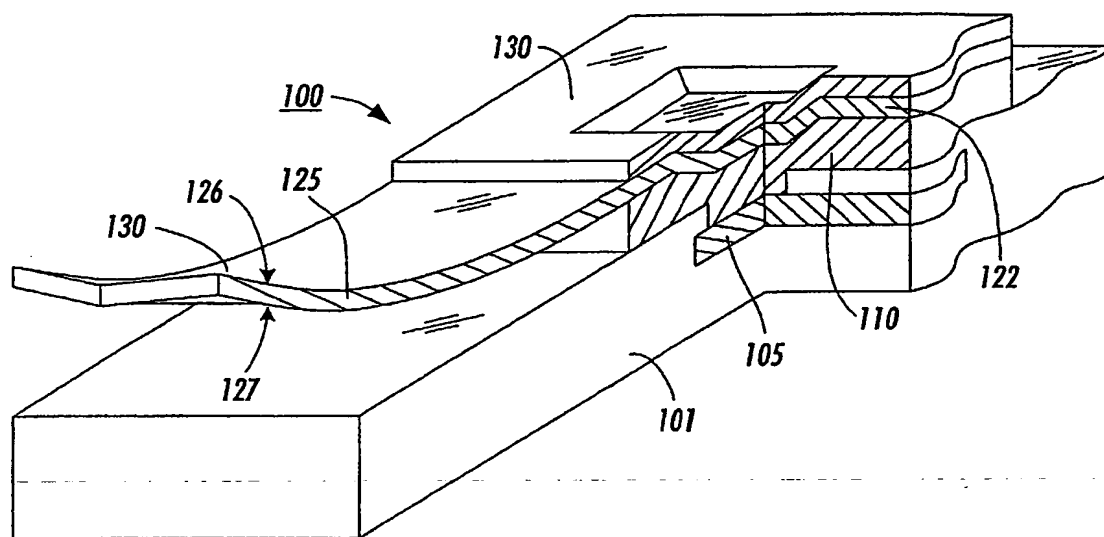


FIG. 4

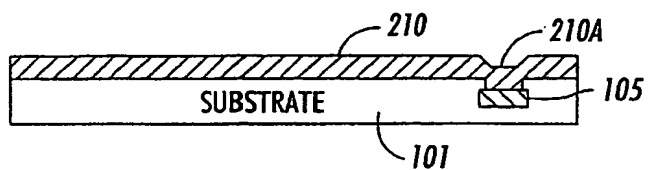


FIG. 5(A)

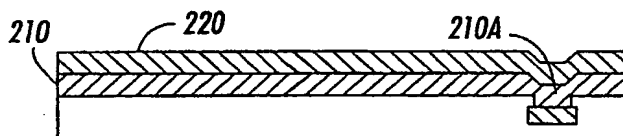


FIG. 5(B)

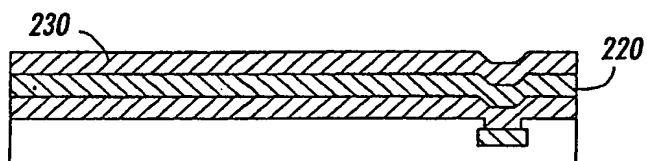


FIG. 5(C)

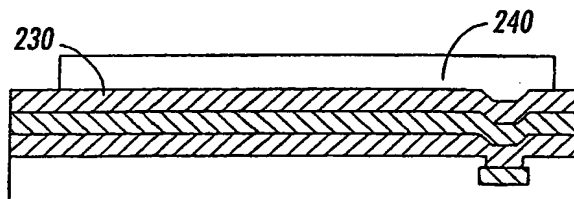


FIG. 5(D)

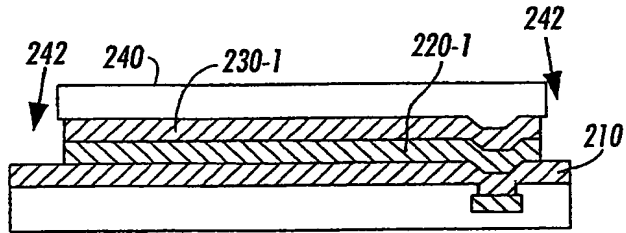


FIG. 5(E)

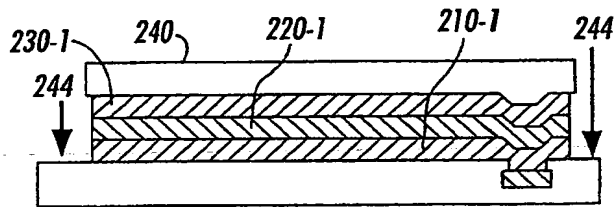


FIG. 5(F)

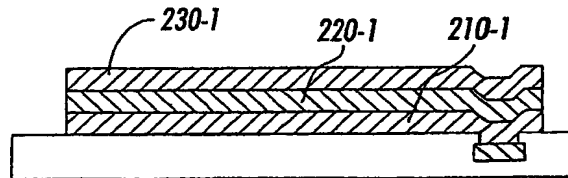


FIG. 5(G)

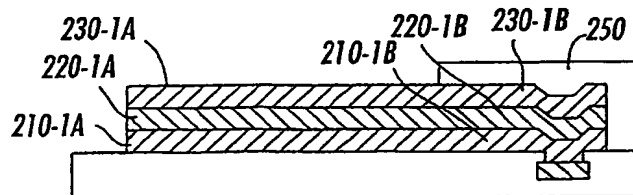


FIG. 5(H)

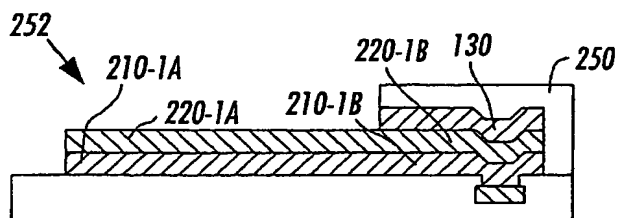


FIG. 5(I)

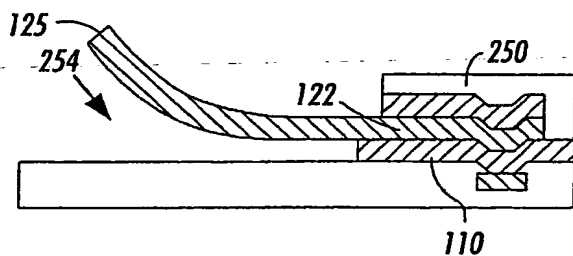


FIG. 5(J)

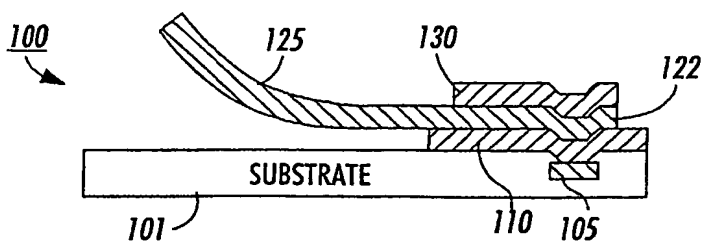


FIG. 5(K)

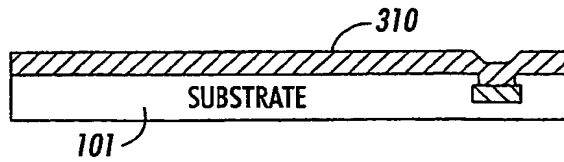


FIG. 6(A)

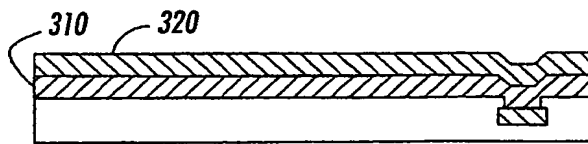


FIG. 6(B)

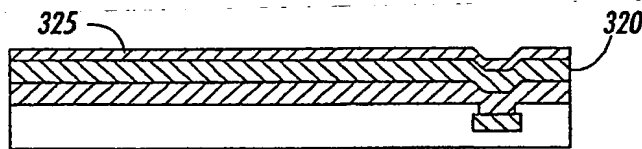


FIG. 6(C)

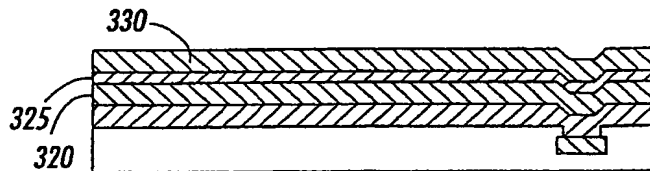


FIG. 6(D)

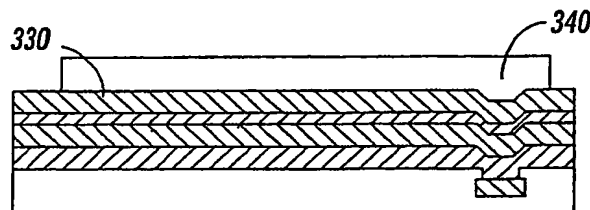


FIG. 6(E)

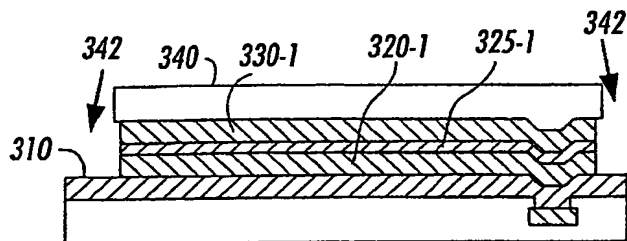


FIG. 6(F)

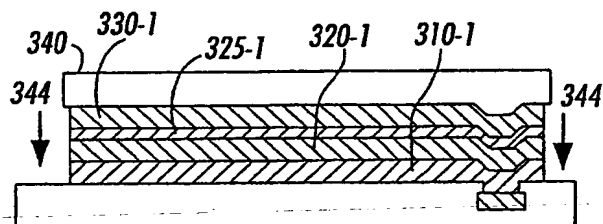


FIG. 6(G)

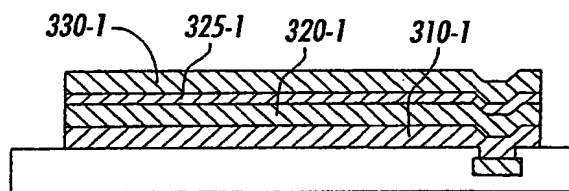


FIG. 6(H)

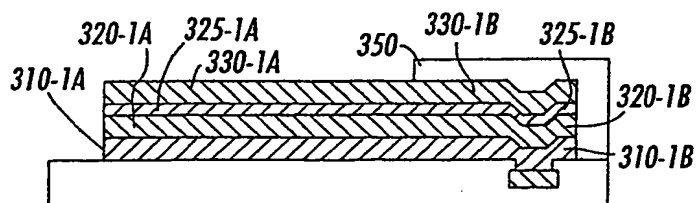


FIG. 6(I)

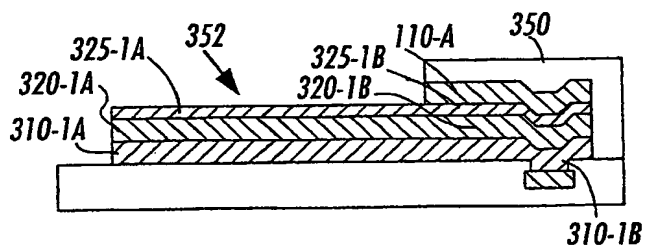


FIG. 6(J)

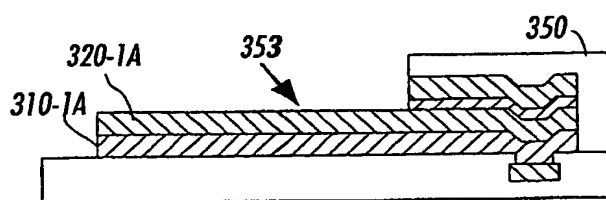


FIG. 6(K)

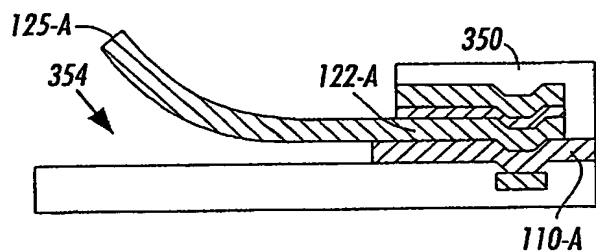


FIG. 6(L)

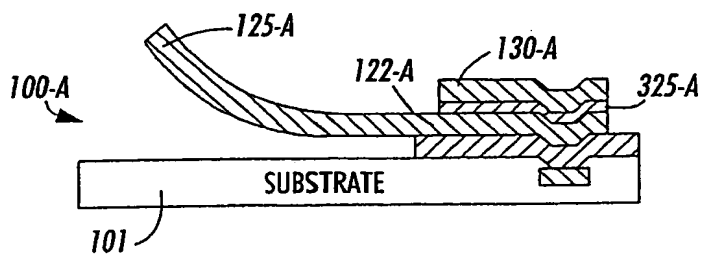


FIG. 6(M)

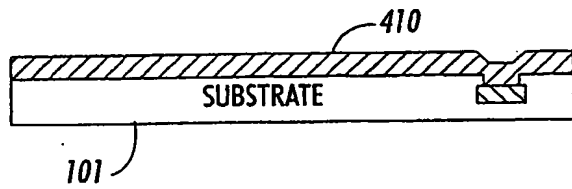


FIG. 7(A)

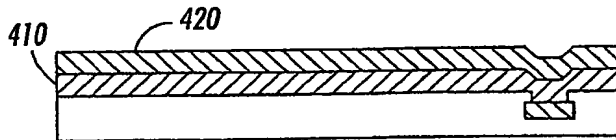


FIG. 7(B)

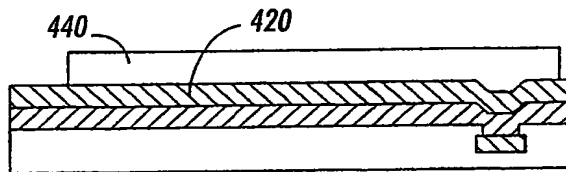


FIG. 7(C)

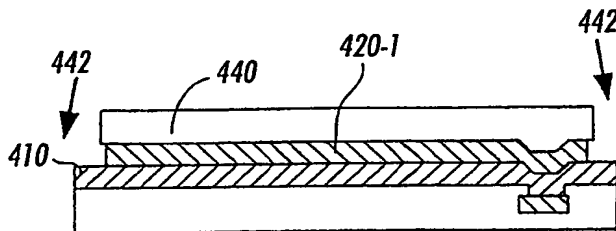


FIG. 7(D)

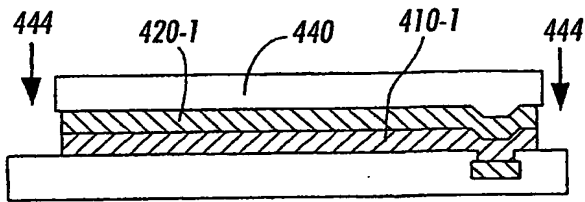


FIG. 7(E)

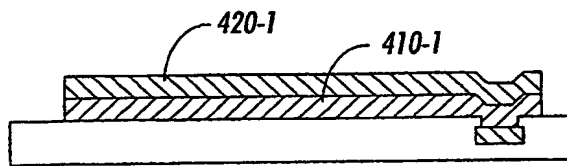


FIG. 7(F)

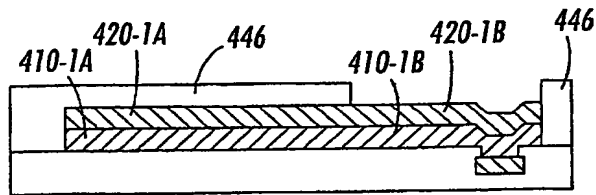


FIG. 7(G)

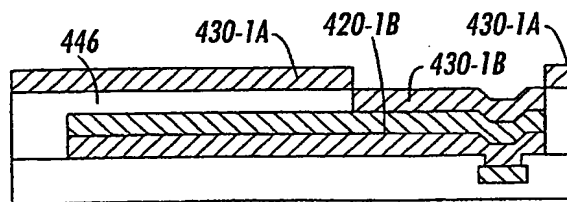


FIG. 7(H)

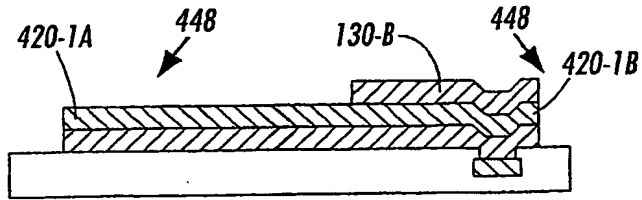


FIG. 7(I)

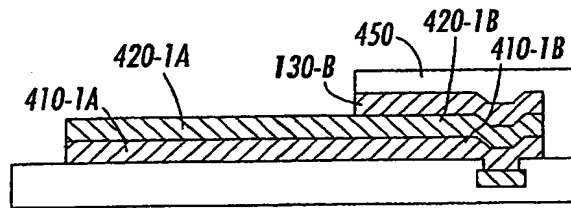


FIG. 7(J)

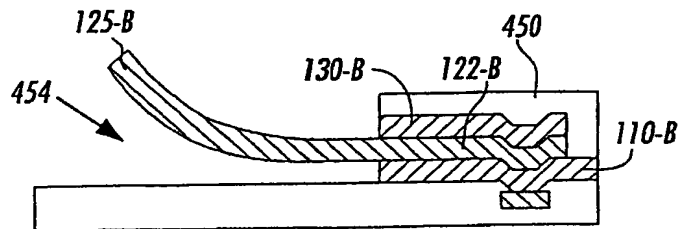


FIG. 7(K)

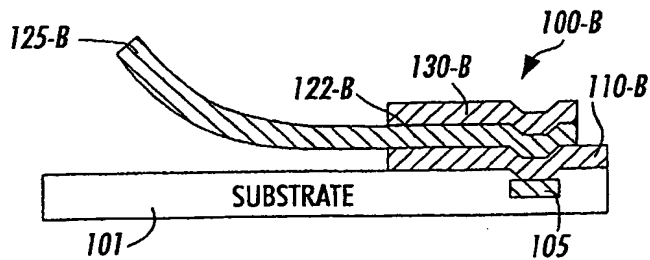
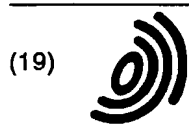


FIG. 7(L)



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(54) **Spring structure**

(57) A stress-balancing layer (130) is formed over portions (122) of a spring metal finger (120) that remain attached to an underlying substrate (101) to counter internal stresses inherently formed in the spring metal finger (120). The (e.g., positive) internal stress of the spring metal causes the claw (tip) (125) of the spring metal finger (120) to bend away from the substrate (101) when an underlying release material is removed. The stress-balancing pad (130) is formed on an anchor portion (122) of the spring metal finger (120), and includes

an opposite (e.g., negative) internal stress that counters the positive stress of the spring metal finger (120). A stress-balancing layer (230) is either initially formed over the entire spring metal finger (120) and then partially removed (etched) from the claw portion (125), or selectively deposited only on the anchor portion (122) of the spring metal finger (120). An interposing etch stop layer (325-1) is used when the same material composition is used to form both the spring metal (220) and stress-balancing (230) layers.

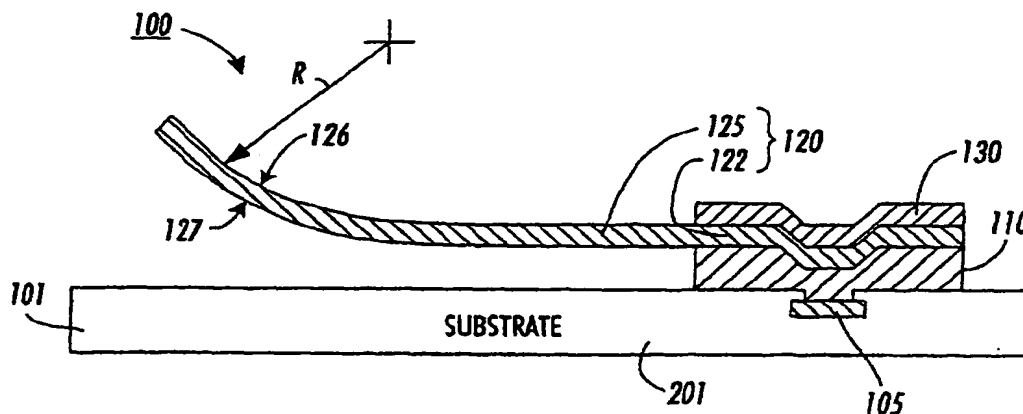


FIG. 2



European Patent
Office

EUROPEAN SEARCH REPORT

Application Number
EP 02 25 6864

DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.7)
A	US 6 290 510 B1 (FORK DAVID KIRTLAND ET AL) 18 September 2001 (2001-09-18) * column 5, lines 25-53; figure 5 *	18	H01R13/22 B81B3/00
A	US 6 236 491 B1 (GOODWIN-JOHANSSON SCOTT HALDEN) 22 May 2001 (2001-05-22) * column 7, line 7 - column 8, line 17; figure 1 *	1-8	
			TECHNICAL FIELDS SEARCHED (Int.Cl.7)
			B81B
The present search report has been drawn up for all claims			
Place of search Berlin		Date of completion of the search 5 December 2003	Examiner Marcolini, P
<p>CATEGORY OF CITED DOCUMENTS</p> <p>X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document</p> <p>T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document</p>			

EPO FORM 1503 (03.02.02) (P4/C01)

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EP 02 25 6864

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05-12-2003

Patent document cited in search report		Publication date	Patent family member(s)	Publication date
US 6290510	B1	18-09-2001	EP 1176635 A2	30-01-2002
			US 2002016095 A1	07-02-2002
			US 2002013070 A1	31-01-2002

US 6236491	B1	22-05-2001	AU 4857800 A	18-12-2000
			CA 2368129 A1	07-12-2000
			EP 1183566 A1	06-03-2002
			JP 2003501274 T	14-01-2003
			WO 0073839 A1	07-12-2000

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